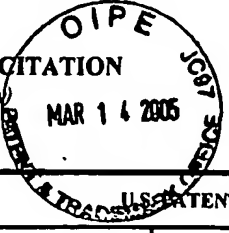


INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>				Docket Number (Optional) 34261-8500		Application Number 10/680,960		
				Applicant(s) Howard Ge et al.				
				Filing Date 10/07/2003		Group Art Unit 1756		
U.S. PATENT DOCUMENTS								
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
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DCD		2002/0092917	7/18/2002	Ko et al.				
FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
DCD		11-010041	19-01-1999	Patent Abstracts of Japan			✓	
DCD		0 654 306	27-05-1994	Europe			✓	
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DCD		KUTCHOUKOV V G ET AL.: "New photoresist coating method for 3-D structured wafers" SENSORS ANDACTUATORS A, ELSEVIER SEQUOIA S.A., LAUSANNE, CHI, vol. 85, no. 1-3, 25 August 2000 pages 377-383.						
EXAMINER /Daborah Chacko-Davis/				DATE CONSIDERED 06/08/2006				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>				Docket Number (Optional)		Application Number	
				34261-8500		10/380,960	
				Applicant(s)			
				Ge et al.			
				Filing Date		Group Art Unit	
				10/07/2003		1756	

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	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
DCD		617,332	09/28/1994	EP				

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DCD		Anonymous, "Process to Clean Metal Surfaces Prior to Photoresist Apply" (XP 007116262A) Research Disclosure – Kenneth Mason Publications, Vol. 324, No. 31, Abstract, April 1991
DCD		Written Opinion of the International Searching Authority, the European Patent Office for the PCT counterpart application PCT/US2004/023587

EXAMINER: /Daborah Chacko-Davis/	DATE CONSIDERED 06/08/2006
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